Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the applications.

Listing of Claims:

Claim 1 (currently amended)

A measuring system of a gas-stream environment, said measuring system ~~comprises~~comprising:

a stage, ~~wherein~~ said stage ~~is located~~locating on a transport apparatus and ~~used to place~~ a wafer placing on said stage;

a datum platen, ~~wherein~~ said datum platen ~~is located~~locating on said transport apparatus and on a side of said stage ~~to be used~~ to place a datum slice;

a lens, ~~wherein~~ said lens ~~is located~~locating above said stage to measure the thickness of said wafer and said datum slice;

a gas supplier, ~~wherein~~ said gas supplier ~~is used to supply~~supplying a gas;

a first gas nozzle, ~~wherein~~ said first gas nozzle ~~is located~~locating on a side of said datum platen;

a second gas nozzle, ~~wherein~~ said second gas nozzle ~~is located~~locating on a side of said stage;

a first tube, ~~wherein~~ said first tube ~~is connected~~connecting with said first gas nozzle and said gas supplier;

a second tube, ~~wherein~~ said second tube ~~is connected~~connecting with said second gas nozzle and with said gas suppler, wherein said gas supplier supplied said gas passing through said first tube and said second tube, and exhausted from said first gas nozzle and said second gas nozzle to form a gas stream;

a transport slot, ~~wherein~~ said transport slot ~~is an opening to exhaust said gas and is used to~~ collecting said gas in said gas stream, and ~~used~~ using ~~to be~~as a channel to exhaust said gas stream; and

a gas-extracting apparatus, ~~wherein~~ said gas-extracting apparatus ~~connects~~ connecting with said transport slot by using a third tube.

Claim 2 (currently amended)

The measuring system according to claim 1, ~~wherein~~ further comprising a

first flow rate regulating valve fixing on said first gas nozzle.

Claim 3 (currently amended)

The measuring system according to claim 1, ~~wherein~~ further comprising a second flow rate regulating valve ~~is fixed~~fixing on said second gas nozzle.

Claim 4 (currently amended)

The measuring system according to claim 1, wherein said gas-extracting apparatus comprises a gas-extracting motor.

Claim 5 (currently amended)

The measuring system according to claim 1, wherein said gas-extracting apparatus comprises a venture structure.

Claim 6 (currently amended)

The measuring system according to claim 1, wherein said gas is an inert gas.

Claim 7 (currently amended)

The measuring system according to claim 1, wherein said gas is nitrogen.

Claim 8 (cancelled)

Claim 9 (currently amended)

A measuring system of a gas-stream environment, said measuring system ~~comprises~~comprising:

a stage, ~~wherein~~ said stage ~~is located~~locating on a transport apparatus and ~~is used to place~~ a wafer placing on said stage;

a datum platen, ~~wherein~~ said datum platen ~~is located~~locating on said transport apparatus and on a side of said stage to ~~be used to~~ place a datum slice;

a lens, ~~wherein~~ said lens ~~is located~~locating above said stage to measure the thickness of said wafer and said datum slice;

a gas supplier, ~~wherein~~ said gas supplier ~~is used to supply~~supplying a gas;

a first gas nozzle, ~~wherein~~ said first gas nozzle ~~is located~~locating on a side of said datum platen;

a second gas nozzle, ~~wherein~~ said second gas nozzle ~~is located~~locating

on a side of said stage;

a first tube, ~~wherein~~ said first tube ~~is connected~~connecting with said first gas nozzle and with said supplier;~~;~~

a second tube, ~~wherein~~ said second tube ~~is connected~~connecting with said second gas nozzle and with said gas supplier, wherein said gas supplier supplied said gas assign through said first tube and said second tube, and exhausted from said first gas nozzle and said second gas nozzle to form a gas stream;

a transport slot, ~~wherein~~ said transport slot ~~is an opening~~extracting said gas; and

a gas-extracting apparatus, ~~wherein~~ said gas-extracting apparatus ~~connects~~ connecting with said transport slot by using a third tube.

Claim 10 (currently amended)

The measuring system according to claim 9, wherein said first tube comprises a first flow rate regulating valve.

Claim 11 (currently amended)

The measuring system according to claim 9, wherein said second tube

comprises a second flow rate regulating valve.

Claim 12 (currently amended)

The measuring system according to claim 9, wherein said gas-extracting apparatus comprises a gas-extracting motor.

Claim 13 (currently amended)

The measuring system according to claim 9, wherein said gas-extracting apparatus comprises a venture structure.

Claim 14(currently amended)

The measuring system according to claim 9, wherein said gas is an inert gas.

Claim 15 (currently amended)

The measuring system according to claim 9, wherein said gas is a nitrogen.

Claim 16 (cancelled)

Claim 17 (currently amended)

A measuring system of a gas-stream environment, said measuring system ~~comprises~~comprising:

a stage, ~~wherein~~ said stage ~~is located~~locating on a transport apparatus and ~~is used to place~~ a wafer placing on said stage;

a datum platen, ~~wherein~~ said datum platen ~~is located~~locating on said transport apparatus and on a side of said stage ~~to be used~~ to place a datum slice;

a lens, ~~wherein~~ said lens ~~is located~~locating above said stage to measure the thickness of said wafer and said datum slice;

a gas supplier, ~~wherein~~ said gas supplier ~~is used to supply~~ supplying a gas in a gas stream;

a first gas nozzle, ~~wherein~~ said first gas nozzle ~~is located~~locating on a side of said datum platen and on said transport apparatus to exhaust said gas ~~in said gas stream~~;

a second gas nozzle, ~~wherein~~ said second gas nozzle ~~is located~~locating on a side of said stage and on said transport apparatus to exhaust said gas in said gas stream;

a first tube, ~~wherein~~ said first tube ~~comprises~~ having a first flow rate regulating valve, and ~~is connected~~connecting with said first gas nozzle and with said gas supplier;

a second tube, ~~wherein~~ said second tube ~~comprises~~ having a second flow rate regulating valve and ~~is connected~~connecting with said second gas nozzle and with said gas supplier;

a transport slot, ~~wherein~~ said transport slot is an opening to exhaust said gas; and

a gas-extracting apparatus, ~~wherein~~ said gas-extracting apparatus ~~connects~~ connecting with said transport slot by using a third tube and ~~is used to produce~~producing an attraction to remove said gas.

Claim 18 (currently amended)

The measuring system according to claim 17, wherein said gas-extracting apparatus comprises a venture structure.

Claim 19 (currently amended)

The measuring system according to claim 17, wherein said gas is an inert gas.

Claim 20 (currently amended)

The measuring system according to claim 17, wherein said gas is nitrogen.

Claim 21 (currently amended)

The measuring system according to claim 1, wherein said first gas nozzle used to exhaust a gas in a gas stream.

Claim 22 (currently amended)

The measuring system according to claim 1, wherein said transport slot used collect said gas in said gas stream.

Claim 23 (currently amended)

The measuring system according to claim 1, wherein said transport slot used to be a channel to exhaust said gas in said gas stream.

Claim 24 (New)

The measuring system according to claim 1, wherein said lens to

measure said thickness of said wafer comprises:

placing said wafer on said stage by using a robot;

moving said stage to the place under said lens by using said transport device;

irradiating a light from said lens to a surface of said wafer and the data, wherein said data returned from said light and showed on a monitor; and

analyzing said data to obtain said thickness of said wafer.

Claim 25 (New)

The measuring system according to claim 9, wherein said lens to measure said thickness of said wafer comprises:

placing said wafer on said stage by using a robot;

moving said stage to the place under said lens by using said transport device;

irradiating a light from said lens to a surface of said wafer and the data, wherein said data returned from said light and showed on a monitor; and

analyzing said data to obtain said thickness of said wafer.

Claim 26 (New)

The measuring system according to claim 17, wherein said lens to measure said thickness of said wafer comprises:

placing said wafer on said stage by using a robot;

moving said stage to the place under said lens by using said transport device;

irradiating a light from said lens to a surface of said wafer and the data, wherein said data returned from said light and showed on a monitor; and

analyzing said data to obtain said thickness of said wafer.